

METHOD OF OPERATING A LITHOGRAPHIC APPARATUS,
LITHOGRAPHIC APPARATUS, METHOD OF MANUFACTURING A DEVICE,
AND DEVICE MANUFACTURED THEREBY

A method of operating a lithographic projection apparatus comprises forming a spot of radiation at the wafer level using a pinhole at reticle level. A sensor is defocused with respect to said spot such that it is spaced apart from said wafer level. The sensor is scanned beneath the spot to measure the angular intensity distribution of radiation at the spot and to determine the intensity distribution at the pupil plane of the projection lens system.